

# Electrical properties of 100-oriented $(1-x)\text{BiFeO}_3\text{-}x(\text{Bi}_{0.5}\text{K}_{0.5})\text{TiO}_3$ thin films on $\text{LaNiO}_3$ electrode

Graduate School of Eng., Osaka Pref. Univ.<sup>1</sup>, Jin Hong Choi<sup>1</sup>, Takeshi Yoshimura<sup>1</sup>,  
and Norifumi Fujimura<sup>1</sup>

E-mail: tyoshi@pe.osakafu-u.ac.jp

## [Introduction]

$\text{BiFeO}_3\text{-(Bi}_{0.5}\text{K}_{0.5})\text{TiO}_3$  (BF-BKT) system is one of the candidate of lead-free piezoelectric ceramics because it is reported that BF-BKT ceramics have large piezoelectric constant ( $d_{33}=370\text{pm/V}$ ).<sup>1)</sup> This result is encouraging for the improvement of piezoelectric constant of Bi-base perovskite ferroelectric thin films.<sup>2)</sup> In this study, we investigate the phase development for crystallization process and electrical properties of BF-BKT thin films grown on (100) oriented  $\text{LaNiO}_3/\text{Si}$ .

## [Experimental Procedure and results]

0.6BF-0.4BKT films were deposited by rf-sputtering method. 0.6BF-0.4BKT ceramic disk with 10% excess Bi prepared by conventional ceramic process was used as a target. The films were grown on (100)  $\text{LaNiO}_3$  (LNO)/Si substrates under the process pressure of 1 Pa with an  $\text{Ar}:\text{O}_2$  ratio of 4:1. The thickness of the films was fixed as  $\sim 240$  nm. Figure 1 show the XRD profiles of 0.6BF-0.4BKT thin films deposited at the substrate temperature between 475 °C and 575 °C. While all the films crystallized in perovskite phase, the integrated diffraction intensities of 200 peaks of the films are highest at 505 °C and the lattice constant decreases with increasing growth temperature. It was also found that the films deposited at higher temperature have the deficiencies of  $\text{Bi}^{3+}$  and  $\text{K}^+$ . The polarization-voltage ( $P$ - $V$ ) hysteresis loop of the films was measured at room-temperature. Although the films deposited above 540 °C do not show the hysteresis behavior, the ferroelectricity is observed for the films deposited at below 505 °C as shown in Fig. 2. It appears this is also caused by the evaporation of  $\text{Bi}^{3+}$  and  $\text{K}^+$  at higher deposition temperature. In the presentation, the piezoelectric properties of the films are also discussed.

## [Reference]

- 1) M. I. Morozov et al., Appl. Phys. Lett. **101**, 252904 (2012).
- 2) C. -J. Cheng et al., Appl. Phys. Lett. **97**, 212905 (2010).

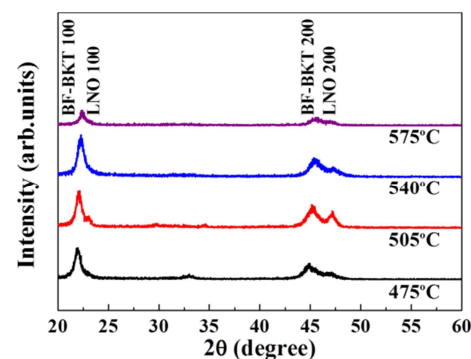


Fig. 1. XRD patterns of a 0.6BF-0.4BKT thin film fabricated on (100) LNO/Si

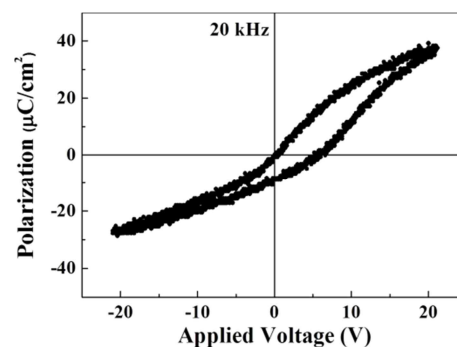


Fig. 2. Ferroelectric  $P$ - $V$  hysteresis loop of the BF-BKT thin film deposited at 505 °C